

IN THE CLAIMS

Please amend claim 6 as indicated below.

This listing of claims will replace all prior versions, and listings, of the claims in the Application.

**Listing of Claims:**

Claim 1 (original) A method for detecting a heat generating failure in a semiconductor device having an unpassivated surface comprising the steps of:

applying a coating to said unpassivated surface of said semiconductor device, wherein said coating is non-electrically conducting and capable of localizing heat generated by said failure in a particular area;

biasing said semiconductor device; and

detecting said failure by detecting a location of said heat generated by said failure in said coating.

Claim 2 (original) The method as recited in claim 1, wherein said coating comprises a high flash point and a low vapor pressure.

Claim 3 (original) The method as recited in claim 1, wherein said coating comprises a liquid.

Claim 4 (original) The method as recited in claim 1, wherein said coating comprises silicon dioxide.

Claim 5 (original) The method as recited in claim 4, wherein said coating has a thickness of approximately two microns.

Claim 6 (currently amended) A semiconductor device comprising:

an unpassivated surface;

~~a failure, wherein said failure being a heat generating failure;~~ and

a coating on said unpassivated surface, wherein said coating is non-

electrically conducting and capable of localizing heat generated by [[said]] a failure in a particular area of said coating, wherein said failure is detected by detecting a location of said heat generated by said failure in said coating.

Claim 7 (original) The semiconductor device as recited in claim 6, wherein said coating comprises a high flash point and a low vapor pressure.

Claim 8 (original) The semiconductor device as recited in claim 6, wherein said coating comprises a liquid.

Claim 9 (original) The semiconductor device as recited in claim 6, wherein said coating comprises silicon dioxide.

Claim 10 (original) The semiconductor device as recited in claim 9, wherein said coating has a thickness of approximately two microns.